EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	276	semiconductor with (fab fabricat\$4) with (simulat\$4 model\$4)	USPAT	OR	OFF	2006/02/20 14:53
L2	6	(fair adj model) or (fair adj diffusion adj model)	USPAT	OR	OFF	2006/02/20 14:53
L3	1	("6154717").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/20 14:53
L4	8	"10/989011" "10/780938" "10/668621" "09/891400" "09/781421" "09/519856"	US-PGPUB; USPAT; USOCR	ÖR	OFF	2006/02/20 14:53
L5	1661	703/2.ccls.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/20 14:53
L6	162	L5 and (diffusion impurit\$3 impure)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/20 14:53
L7	200	("pile-up" (pile adj up)) same (diffusion diffus\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/20 14:53
L8	1	10/059176	US-PGPUB	OR	OFF	2006/02/20 14:53
L9	1	"6581028".pn.	USPAT	OR	OFF	2006/02/20 14:53
L10	258	reverse adj short adj channel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/20 14:53
L11	21	("5930494" "5819073" "5557710" "5684723" "6195790" "5148379" "6360190" "6242272" "6006026" "6080200" "5828586" "5889687" "6185472" "5819073" "6041424" "4584662" "6182270" "6011914" "6144932" "6360190" "6154717" "6505147" "6144929").pn.	USPAT	OR	OFF	2006/02/20 14:53
L12	13	("5103415" "5671395" "5675522" "5677846" "5774696" "5784302" "5819073" "5828586" "5889680" "5930494" "5963732" "6006026" "6011914").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/20 14:53

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L13	19	(US-4607530-\$ or US-6594625-\$ or US-6006026-\$ or US-6684181-\$ or US-6327555-\$ or US-6285970-\$ or US-6154718-\$ or US-6154717-\$ or US-6148276-\$ or US-6144929-\$ or US-6120548-\$ or US-6999719-\$ or US-6581028-\$ or US-5557710-\$ or US-6242272-\$ or US-6505147-\$ or US-5889687-\$ or US-5930494-\$).did.	USPAT	OR	OFF	2006/02/20 14:53
L14	1	L13 and (SiO)	USPAT	OR	OFF	2006/02/20 14:53
L15	9	L13 and layer	USPAT	OR	OFF	2006/02/20 14:53
L16	5	L13 and (source drain)	USPAT	OR	OFF	2006/02/20 14:53
L17	4	L16 and distance	USPAT	OR	OFF	2006/02/20 14:53
L18	1	"6080200".pn.	USPAT	OR	OFF	2006/02/20 14:53
L19	266	(impurity adj diffusion) same (source drain) same (distance length)	USPAT	OR	OFF	2006/02/20 14:53
L20	41	L19 and (simulat\$4 model\$4)	USPAT	OR	OFF	2006/02/20 14:53
L21	266	(impurity adj diffusion) same (source drain) same (distance length)	USPAT	OR	OFF	2006/02/20 14:53
L22	20	(US-4607530-\$ or US-6594625-\$ or US-6006026-\$ or US-6684181-\$ or US-6327555-\$ or US-6285970-\$ or US-6154718-\$ or US-6154718-\$ or US-6148276-\$ or US-6144929-\$ or US-6120548-\$ or US-6041174-\$ or US-5999719-\$ or US-6581028-\$ or US-5557710-\$ or US-6242272-\$ or US-6505147-\$ or US-5889687-\$ or US-5930494-\$ or US-6080200-\$). did.	USPAT	OR	OFF	2006/02/20 14:53

2/20/2006 3:00:29 PM C:\Documents and Settings\asaxena\My Documents\EAST\Workspaces\10059176.wsp Page 2



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New Search		Check to search only within this results set				
» Key		Display Format:				
IEEE JNL	IEEE Journal or Magazine	view selected items Select All Deselect All				
IEE JNL	IEE Journal or Magazine					
IEEE CNF	IEEE Conference Proceeding	 Parasitic energy barriers in SiGe HBTs Slotboom, J.W.; Streutker, G.; Pruijmboom, A.; Gravesteijn, D.J.; 				
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